

IDS - 05/11/2006 <b>INFORMATION DISCLOSURE CITATION</b> <i>(Use several sheets if necessary)</i>	Docket number (Optional) <b>15689.49.6</b>	Application Number <b>10/673,685</b>
	Applicant(s) <b>Takehiro Nakamura et al.</b>	
	Filing Date <b>September 29, 2003</b>	Group Art Unit <b>2638</b>

U.S. PATENT DOCUMENTS							
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

U.S. PATENT APPLICATION PUBLICATIONS							
*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS								
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
KK	1	0 682 418 A2	05/12/1995	EPO	H0487	005	X	
KK	2	CN1126930	7/17/1996	China	H04B7	005	X	

EXAMINER  /Kevin Kim/ (05/31/2006)	DATE CONSIDERED
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EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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*Examiner Initial	OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)	
KK	3	Chinese Office Action for Chinese Patent Application No.: 20031010330.1
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